

Pos	Qty	Description
1	1	<p>SUSS MA6 ALIGNER TSA/BSA - Remanufactured to new condition basic system prepared for manual alignment stage with:</p> <ul style="list-style-type: none"> - automatic wedge compensation system in contact or without contact between mask and wafer (with reference balls), <p>alignment gap programmable from 1 to 1000 micron, resolution 1 micron</p> <ul style="list-style-type: none"> - movement range: X +/-10.0mm, Y +/-5.0mm, Theta +/-5° <p>basic equipment consisting of:</p> <ul style="list-style-type: none"> - machine base with mechanical, pneumatic and electrical equipment 230V/50Hz and 115V/60Hz - adapter system for mask holders for use in combination with mask holders for masks up to 7" x 7" max. - TSA microscope stage with motorized X-Y-manipulator and manual rotation for microscope - with integrated microscope tilt for exposure and to create access for mask loading - prepared for fixed exposure unit - manual loading and unloading of wafers or substrates - microprocessor control with LCD display - for wafers 2" up to 150 mm dia. or substrates 2" x 2" up to 6" x 6" - operator manual in English - prepared for BSA microscopes with working distance 26mm - among other things to be ordered separately: - manual alignment stage system dependent on necessary BSA microscope objective separation - TSA and/or BSA scopes - exposure unit, lamp and optics - mask holders and chucks - other accessories are available
2	1	<p>EXPOSURE UNIT MA6/BA6/350W</p> <ul style="list-style-type: none"> - Optics housing and mirror housing with ellipsoidal mirror and surface mirror - For wafer/substrate sizes up to 150mm diameter / 6" x 6" - For exposure lamps up to 500W possible - Prepared for use in combination with exposure optics optimized for high uniformity and high intensity for various wavelengths and applications: - Range of wavelengths: 250nm to 435nm with 350 W lamps - With components for optimized diffraction reduction for high resolution proximity or contact printing <ul style="list-style-type: none"> - For large gap exposure or thick resists
3	1	<p>BOTTOM SIDE ALIGNMENT SYSTEM' MA6/BA6/BA8 AA=26 FOR DVCU- SYSTEM</p> <ul style="list-style-type: none"> - two special video microscopes with one magnification 128X/410X (refers to 17" monitor) - motorized stages - separation in X: 15mm ...100mm - travel in Y: - 20mm to + 50mm - motorized focus 6mm - two 1/2" CCD video cameras
4	1	<p>LAMP ADAPTER LH350/HBO350W/S</p>

5	1	HG LAMP 350W / Osram
6	1	OPTICS UV400/W-150/LH350 Consisting of: <ul style="list-style-type: none"> - Cold light mirror no 1 100x115mm - Fly's eye - Condensor lens, Herasil, dia. 55mm - Two lens plates, Herasil, conf. A - Font lens, transparent, dia. 180mm
7	1	LAMP POWER SUPPLY UNIT CIC1200 FOR LH350 <ul style="list-style-type: none"> - Constant light intensity mode - Constant power mode - For the DC lamps 200W, 350W/S, 500W, XE 500W - Operation of additional lamp with a current of up to 35A possible (has to be specified and agreed upon) - Easy operation due to microprocessor control - Simultaneous digital display of light intensity and lamp power - Integrated connector for UV-probe for easy calibration - Dual channel mode for 2-channel light sensors with various wave-lengths - Interlock for machine and lamp protection - For input voltages of 230V +/- 10%, 50/60Hz - Power consumption: maximum 2300 VA - Single pulse ignition ensures gentle operation, provides easy lamp start and increases lamp durability
8	1	SUSS 2-CHANNEL LIGHT-SENSOR 365/405NM FOR CIC <ul style="list-style-type: none"> - For lamp power control - Installed inside mirror house
9	1	ALIGNMENT STAGE MA/BA6-8/WD-26/MAN <ul style="list-style-type: none"> - X-Y-THETA alignment stage with high precision micrometer screws for manual alignment - WEC Head for BSA microscope objective separation in X direction from 15mm to 100mm - motorized Z axis
10	1	ENHANCED IMAGE STORAGE SYSTEM DVCU FOR MA8/BA6 image storage and fine focus controller for simultaneous focused images of mask and wafer for easy and precise alignment with large object magnification or large alignment gaps <ul style="list-style-type: none"> - PC with image and fine focus control - for M306/8, DVM6/8 and BSA 17" TFT flat screen - integrated trackball - 5-VGA resolution 1280x1024 - contrast integration function for pure contrast images - electronic brightness. contrast and magnification adjustment - adjustment of brightness ratio stored/live image
11	1	SUSS M336 MICROSCOPE DVM
12	1	MICROSCOPE ILLUMINATION 85W/M500/M306/MA6/BA6/LH350 <ul style="list-style-type: none"> - With yellow filter - Halogen-illumination 13.8V/85W to be attached to MA6/BA6 with LH350

13	1	SET OF TURRETS FOR 3 OBJECTIVES DVM6/8
14	1	OBJECTIVE LMPL 10XIR/0.30
15	1	SUSS UV OPTOMETER CASE CPL. <ul style="list-style-type: none"> - For intensity and intensity uniformity calculation - Dose measurement functionality - To be ordered with SUSS OPTOMETER probe (365/405nm: G187080) - Storage case for measurement system and probes
16	1	SUSS UV LIGHT MEASURING PROBE 365/405NM for UV OPTOMETER <ul style="list-style-type: none"> - Combined 2 channel probe 365/405nm - Improved measurement accuracy and repeatability - Improved shock resistance - only in combination with SUSS UV OPTOMETER (G207355)
17	1	CHUCK MA6/ BA6/VAC/BSA/W-100 <ul style="list-style-type: none"> - For wafer dia. 100mm - For proximity, soft - and vacuum contact exposures - With 2 openings for viewing of alignment pattern X=32mm x Y=20mm - Center position of openings Xl/r=t30mm Y=0 (relative to chuck center) - With prealign pins - for Top Side and Bottom Side Alignment
18	1	MASK HOLDER MA6/ BA6/ BL/PROX/CONT/M-5-6/W-100 <ul style="list-style-type: none"> - Bottom loading - Contact/proximity wedge-error-compensation - For masks from 5"x5" to 6"x6" - Exposure opening for wafers dia. 100mm - With displaceable stop pins - With displaceable additional mechanical clamping
19	1	SUSS MA6/BA6 VIBRATION ISOLATION AND DAMPING SYSTEM <ul style="list-style-type: none"> - Antivibration machine base frame / black - Dimension: 930mm x 950mm x 705mm - One shelf 280mm x 700mm, height adjustable - Three covers right, left and backside - Four wheels - Handrest for ergonomic operation of the machine - Pneumatic vibration isolation and automatic height control - Vertical frequency of resonance: < 2Hz at rated load - Horizontal frequency of resonance: < 1,8Hz at rated load - Improved horizontal damping - Max. load: 590kg - Vertical adjustment stands - Suitable for cleanroom class 100
20	1	OPERATOR'S MANUAL MA6 MA8 BA6 BA8 ENGLISH FOR CLEANROOM <ul style="list-style-type: none"> - Additional operator's manual in English